

Lifting Lotion

ID	FACE Care / 700481.0001	ID-No: 001.001
pH-value	5.0 - 5.5	
Appearance	Slightly yellowish emulsion	
Product Form	Emulsion O/W	
Claims	Caring; Microplastic-free; Moisturising; Natural	

St	Substance	INCI Name USA	% w/w	Manufacturer
1	Water demin.	Water	66.10	several
	Dermosoft Pentiol eco	Pentylene Glycol	3.00	Evonik, DE
	Dermosoft 1388 ECO	Glycerin, Water, Sodium Levulinate, Sodium Anisate	3.00	Evonik, DE
2	Keltrol CG-SFT	Xanthan Gum	0.50	CP Kelco, US
	Kelcogel CG-HA	Gellan Gum	0.10	CP Kelco, DE
3	WITARIX MCT 60/40 coconut based	Caprylic/Capric Triglyceride	17.00	IOI OLEO GmbH, DE
	Dermofeel Toco 70 non-GMO	Tocopherol, Helianthus Annuus (Sunflower) Seed Oil	0.20	Evonik, DE
	Tego Alkanol 1618	Cetearyl Alcohol	1.00	Evonik, DE
	Tegin M Pellets	Glyceryl Stearate	2.00	Evonik, DE
	Tego Care PSC 3	Polyglyceryl-3 Dicitrate/Stearate	3.00	Evonik, DE
4	Citric Acid solution 10%	Citric Acid, Water	1.00	several
5	Perfume Freschezza R458	Fragrance	0.10	Huber the Nose, CH
6	LIFTONIN®-QI	Propanediol, Water, Ganoderma Lucidum (Mushroom) Stem Extract, Citric Acid	3.00	RAHN AG, CH

Production

Mix 2 and add to 1 while stirring, the phase must be homogenous / Heat to 75°C / Mix 3 and heat to 75°C while stirring / Add 1&2 to 3 while stirring strongly, homogenise and cool to 40°C while stirring / Add the remaining ingredients separately, homogenise strongly, cool to 25°C while stirring.

Stability: Stable for more than 3 months at 5°, 25°, 40°C

Microbiological Stability: ---

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